CuLox Silver Powder Photovoltaic



CuLox Fines (0.5, 1, 2 micron) 0005, 0010, 0020

CuLox Fines High Density (0.5, 1, 2 micron) 0005HD, 001HD, 0020HD

CuLox Fines—Flakes (3 micron) 0030F

Description

High purity fine silver particulates with critically controlled size, density and morphology. Designed for low temperature fired flexible substrates in solar cells.

General Application

Conductive paste and inks for photovoltaic applications in thin film and polycrystalline silicon solar cells.

Nominal Chemistry (Impurity Levels, wt%)

Nominal Chemi	stry								
(Levels of	Producto	Regular Powders			High Density Powders			Flakes	
impunty, wt/0)	Fioducis	0005	0010	0020	0005HD	0010HD	0010HD	0030F	
	Ag (minimum)	99.8	99.8	99.8	99.8	99.85	99.85	99.9	
	Total Heavy Metals max (Cu, Ni, Pb, Fe)	0.02	0.02	0.02	0.02	0.02	0.02	0.02	
	Alkali Metals (combined)	0.01	0.01	0.01	0.01	0.01	0.01	0.005	
	Weight loss (1000°F)	1.2	2.5	2.5	1.2	1.7	1.7	0.9	

Typical SEM

Purity



Typical SEM Photo of Silver Powder (0020) 2 Micron Powder



Typical SEM Photo of Silver Powder (0020HD) 2 Micron High Density



Typical SEM Photo of Silver Flake (0030F) 3 Micron Flake

Physical
Properties

Products	Regular Powders			High	Flakes		
Troducts	0005	0010	0020	0005HD	0010HD	0020HD	0030F
Size (D ₅₀) (Microtrac)	0.25-1.0	1.0-2.0	1.50-3.0	0.4-1.2	0.7-1.8	1.3-3.2	3-5
Specific Surface Area (m ² /g)	1.0-2.5	1.0-3.0	0.25-1.50	1.0-2.6	0.5-1.2	0.3-0.7	0.6-1.2
Tap Density (gm/cc)	1.25-3.0	2.0-4.5	3.0-5.0	1.6-3.0	3-5	3.5-5.5	2.5-4.0
Apparent Density (g/in ³)	9-20	20-48	22-51	18-28	30-50	44-64	28-38

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